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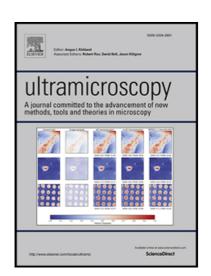
Focused Ion Beam-Assisted Fabrication of Soft High-Aspect-Ratio Silicon Nanowire Atomic Force Microscopy Probes

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Highlights

- Soft high-aspect ratio probes for PeakForceTM tapping AFM
- Material independent platinum-catalyzed silicon nanowire growth on commercial AFM probes
- Nanowire orientation and tilt-compensation using focused Ga⁺ ion beam
- Imaging of optical diffraction gratings milled in GaAs and silver halides with simultaneous adhesion mapping

Chillip Martin

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